IAP5 Rec'd PCT/PTO 01 SEP 2006

Receipt date: 09/01/2006 10591476 - GAU: 1792

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OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.) AQ Per Martensson et al., "Growth and Selectivity in the Cu(II) - 2.2.6.6-tetramethyl-3.5heptanedionate/H₂ Process", Journal of the Electrochemical Society, 1998, Vol. 145, No. 8, pp. 2926-2931 AR Mikko Utriainen, et al., "Studies of metallic thin film growth in an atomic layer epitaxy reactor using M(acac)₂ (M=Ni, Cu, Pt) precursors, Applied Surface Science, 2000, vol. 157, pp. 151-158 AS

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